PROCESS FOR CREATING LITHOGRAPHICALLY-DEFINED PLASMONIC STRUCTURES WITH ENHANCED Q FACTORS

ABSTRACT

A method for plasmonic structure manufacture and for protecting a plasmonic nanostructure during annealing is provided. The method includes: lithographically forming a plasmonic nanostructure on a substrate; encapsulating the plasmonic nanostructure in high temperature resistant material; annealing the plasmonic nanostructure; and removing the high temperature resistant material to reveal the annealed plasmonic nanostructure.

FIGURE 1